KMnF₃: Yb³⁺, Er³⁺ @ KMnF₃: Yb³⁺ active-core-active-shell nanoparticles with enhanced red up-conversion fluorescence for polymer-based waveguide amplifiers operating at 650nm

Yongling Zhang,¹ Fei Wang,¹ Yanbo Lang, Jiao Yin, Meiling Zhang, Xiaohui Liu, Daming Zhang, Dan Zhao*, Guanshi Qin*, 5 Weiping Qin*

¹These authors contributed equally to this work.

Received (in XXX, XXX) Xth XXXXXXXX 20XX, Accepted Xth XXXXXXXX 20XX DOI: 10.1039/b000000x

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Supporting information



Fig. S1 Synthetic Procedure for the KMnF₃: Yb³⁺, Er³⁺ Core Nanoparticle.



Fig. S2 Synthetic Procedure for the KMnF₃: Yb³⁺, Er³⁺ @ KMnF₃: Yb³⁺ Core–Shell Nanoparticle.



Fig. S3 The energy-dispersive X-ray spectrum of the KMnF₃: 18% Yb³⁺, 1% Er³⁺@ KMnF₃: 2% Yb³⁺ NPs.



Fig. S4 (a) UC emission spectra of KMnF₃: x% Yb³⁺, 1% Er³⁺ NPs. (b) Intensity enhancement of UC emission depending on the Yb³⁺ concentrations in the KMnF₃: x% Yb³⁺, 1% Er³⁺ (x=5, 10, 15, 18, 20, 25, 30) NPs.



Fig. S5 The FTIR spectrum of the KMnF₃: 18% Yb³⁺, 1% Er³⁺@ KMnF₃: 2% Yb³⁺ (active-core-active-shell) NPs.

The active-core-active-shell NPs of KMnF₃: 18 mol% Yb³⁺, 1 mol% Er³⁺@KMnF₃: 2 mol%Yb³⁺ can be dispersed in nonpolar solution, because of there are hydrophobic OA ligands capping on the NPs. To clarify it, we measured the 5 FTIR spectrum of KMnF₃: 18 mol% Yb³⁺, 1 mol% Er³⁺@KMnF₃: 2 mol%Yb³⁺ NPs, as shown in **Fig. S5**. The peaks at 2856 cm⁻¹ and 2925 cm⁻¹ are corresponding to the symmetric and asymmetric stretching of the methylene (CH₂) in the aliphatic chain of the oleic acid coating, respectively. The absorption peaks at 1545 cm⁻¹ and 1464 cm⁻¹ can be ascribed to the asymmetric and symmetric stretching vibrations of carboxylate anions bound to the surface of KMnF₃: 18 mol% Yb³⁺, 1 mol% Er³⁺@KMnF₃: 2 mol%Yb³⁺ NPs. Therefore, the NPs can be dispersed in nonpolar solvent 10 (cyclohexane and toluene).



Fig. S6 Fabrication process for waveguide amplifier. (a) spin-coat and cure PMMA bottom cladding layer, evaporate AI mask, spin-coat and cure BP212 photoresist. (b) photolithography. (c) wet etching. (d) ICP etching, then remove the remaining AI mask and BP212. (e) spin-coat and KMnF₃: 18 mol% Yb³⁺, 1 mol% Er³⁺ @ KMnF₃: 2 mol% Yb³⁺ NPs dispersed PMMA material. (f) spin-coat and cure PMMA cladding cladding layer.

The polymer-based waveguide amplifier was manufactured in three steps. Firstly, a PMMA film as bottom cladding layer was spin-coated onto a silicon dioxide layer based on silicon substrates, and cured at 120°C for 2 h. The 5 waveguide pattern was fabricated by standard photolithography and ICP (inductively coupled plasma) etching technique using oxygen on the cladding layer. Secondly, the KMnF₃: 18 mol% Yb³⁺, 1 mol% Er³⁺ @ KMnF₃: 2 mol% Yb³⁺ NPs dispersed PMMA was embedded into the grooves to constitute the core waveguides using spin-coating, and the device was baked at 100°C for 2.5 h. Thirdly, a PMMA film was spin-coated as the upper cladding and baked at 120 °C for 2 h.